

Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No. MAT-9 Applicants: Timans et al Filing Date July 28, 2003	Serial No.: 10/629,400 Group 2812
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U.S. Patent Documents

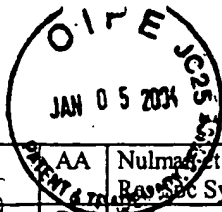
Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
Jef	A	4,938,815	7/3/1990	McNeilly			
	B	4,579,080	4/1/1986	Martin et al			
	C	5,561,735	10/1/1996	Camm			
	D	5,971,565	10/26/1999	Zapata et al			
	E	5,874,711	2/23/1999	Champetier et al			
	F	5,960,158	9/28/1999	Gat et al			
	G	5,997,175	12/7/1999	Champetier et al			
	H	6,027,244	2/22/2000	Champetier et al			
	I	6,056,434	5/2/2000	Champetier			
	J	6,127,658	10/3/2000	Kohav			
	K	6,303,411	10/16,2001	Camm et al			
	L	6,534,752	3/18/2003	Camm et al			
	M	6,594,446	7/15/2003	Camm et al			
	N	US2002/0102098 A1	8/1/2002	Camm et al			

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
Jef	O	WO 03/060447 A1	7/24/2003	Canada			Yes	No

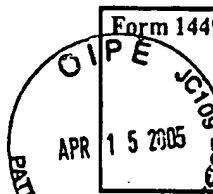
Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
Jef	P	Knutson et al, Modeling Of Radiation Heat Transfer And Wafer Temperatures In A Complex Three-Dimensional Rapid Thermal Processing Chamber, 8/31/1994, 2 nd International Rapid Thermal Processing Conference, Monterey California
	Q	Burggraaf, Rapid Wafer Heating: Status 1983, 12/1983, Semiconductor International, pp69-74
	R	Gelpey et al, Process Control for a Rapid Optical Annealing System, 1986, Mat Res Soc Symp Proc, Vol 52, Materials Research Society
	S	Wilson et al, an Overview and Comparison of Rapid Thermal Processing Equipment: A Users Viewpoint, 1986, Mat Res Soc Symp Proc, Vol 52, Materials Research Society
	T	Blake et al, Slip Free Rapid Thermal Processing, 1987, Mat Res Soc Symp Proc, Vol 92, Materials Research Society
	U	Celler et al, Drift of Arsenic in SiO ₂ in a Lamp Furnace with a Built-in Temperature Gradient, 1987, Mat Res Soc Symp Proc, Vol 92, Materials Research Society
	V	Lord, Thermal and Stress Analysis of Semiconductor Wafers in a Rapid Thermal Processing Oven, August 1988, IEEE Transactions on Semiconductor Manufacturing, Vol 1, No 3, pp103-114
	W	Hill et al, Reduced Thermal Processing for ULSI, 1989, Plenum Press, pp 143-180
	X	Kakoschke, Is There a Way to a Perfect Rapid Thermal Processing System?, 1991, Mat Res Soc Symp Proc, Vol 224, Materials Research Society, pp 159-170
	Y	Kakoschke, Simulation of Temperature Effects During Rapid Thermal Processing,, 1989, Mat Res Soc Symp Proc, Vol 146, Materials Research Society, pp 473-483
Jef	Z	Vandenabeele et al, Impact of Patterned Layers on Temperature Non-uniformity During Rapid Thermal Processing for VSLI-Application, 1989, Mat Res Soc Symp Proc, Vol 146, Materials Research Society, pp 149-160



STH	AA	Nulman et al, Pyrometric Emissivity Measurements and Compensation in an RTP Chamber, 1989, Mat Res Soc Symp Proc, Vol 146, Materials Research Society, pp 461-466
	BB	Dilhac et al, Adaptive Process Control for a Rapid Thermal Processor, 1990, SPIE, Vol 1393, Rapid Thermal and Related Processing Techniques, pp 395-403
	CC	Dilhac et al, Thermal Model for Rapid Thermal Processors: Theory and Applications, 9/8/1993, 1 st International Rapid Thermal Processing Conference, Scottsdale, Arizona
	DD	Wei et al, Transient Processing of Titanium Silicides in a Non-Isothermal Reactor, 1985, Mat Res Soc Symp Proc, Vol 35, Materials Research Society, pp 465-470
	EE	Pettibone et al, The Effect of Thin Dielectric Films on the Accuracy of Pyrometric Temperature Measurements, 1986, Mat Res Soc Symp Proc, Vol 52, Materials Research Society, pp 210-216
V	FF	Dilhac et al, Thermal Modeling of a Wafer in a Rapid Thermal Processor, 11/1995, IEEE Transactions on Semiconductor Manufacturing, Vol 8, No 4, pp 432-439
STH	GG	Henda et al, Investigation of the Thermal Behavior of a RTP Furnace, 8/1995, IEEE Transactions on Semiconductor Manufacturing, Vol 8, No 3, pp 362-365
Examiner		Date Considered
Shawntina Lewis		5/20/05

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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<i>gk</i>		5,219,786	6/15/1993	Noguchi			
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<i>gk</i>		5,960,158	9/28/1999	Gat et al			

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Other Documents

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<i>Shawntina Inguva</i>	<i>5/20/05</i>	

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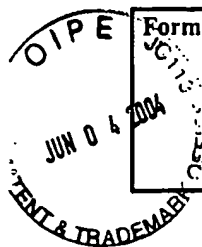
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<i>Shavon L. Liguia</i>	<i>5/20/05</i>	

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gk		US2004/0079746	4/29/2004	Jennings et al			

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				Canada			Yes	No

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Examiner <i>Shawntina Igua</i>		Date Considered <i>5/20/05</i>

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